

METHOD OF MANUFACTURING SUBSTRATE

ABSTRACT

A glass substrate, a resin substrate, a metal substrate or a ceramic substrate having an impurity content of 10 – 50% by weight is used as substrate 1. SiO_2 film 2 is formed on substrate 1 via a liquid phase deposition process. Concavo-convex shape 4 is formed on SiO_2 film 2 by forming etching mask 3 having predetermined patterns on SiO_2 film 2, and dry-etching SiO_2 film 2.

Figure 1